

# High Efficiency Micro-inductors on Silicon

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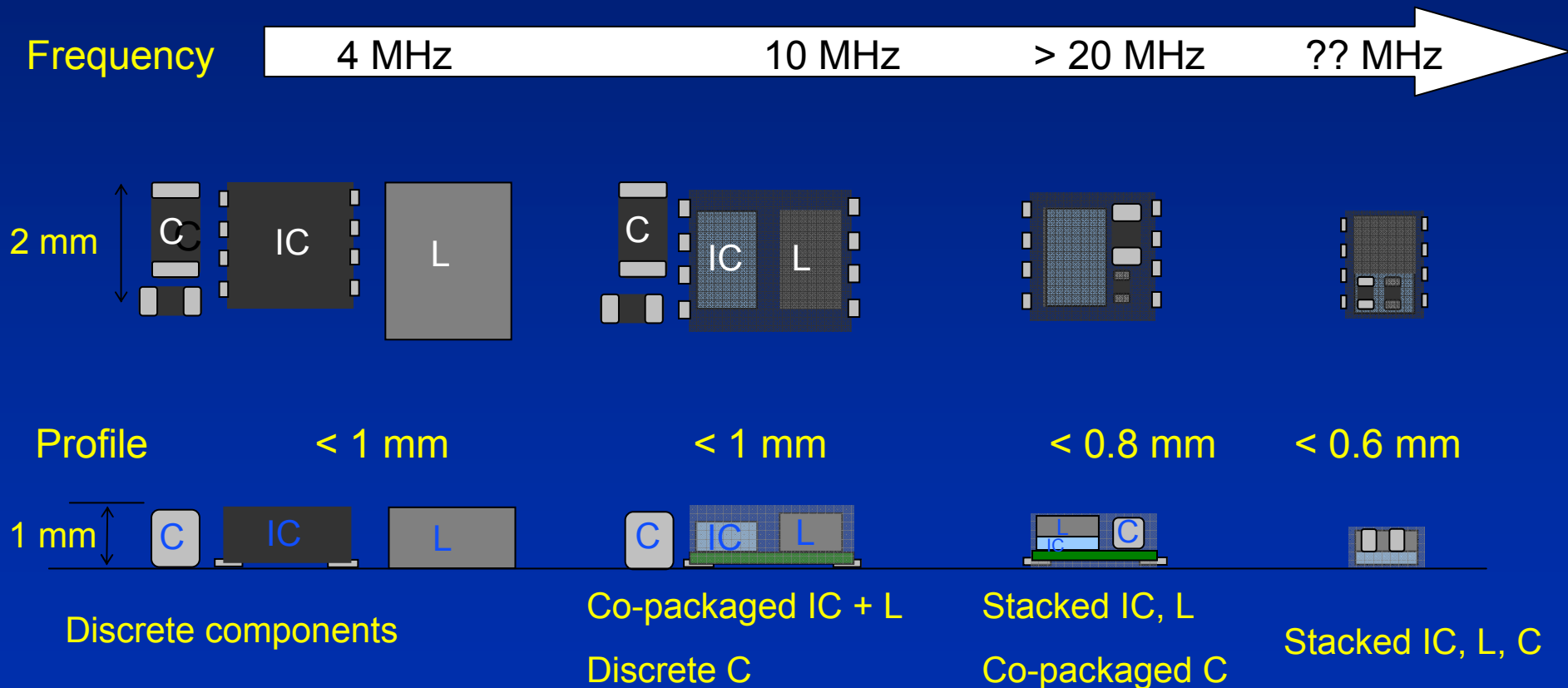


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# Overview

- Why micro-inductors on Silicon?
- Overview of micro-inductor technology
- Design approach and goals
- Results from fabricated devices
- Summary

# Size Reduction with frequency

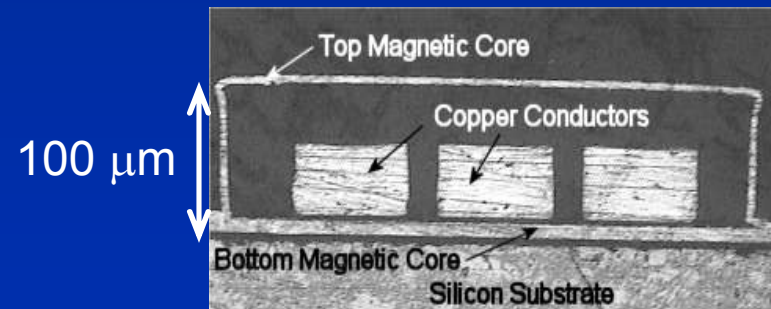
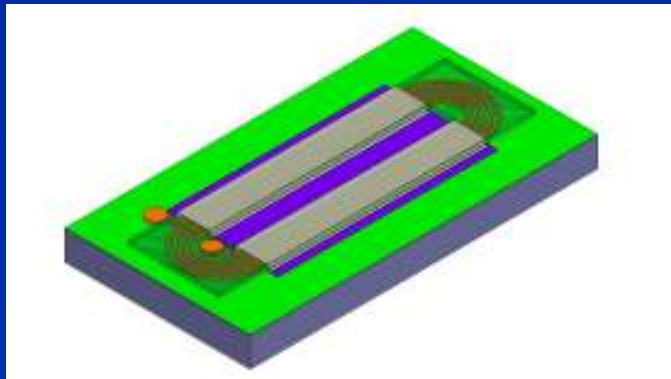


# Why Micro-inductors on Silicon?

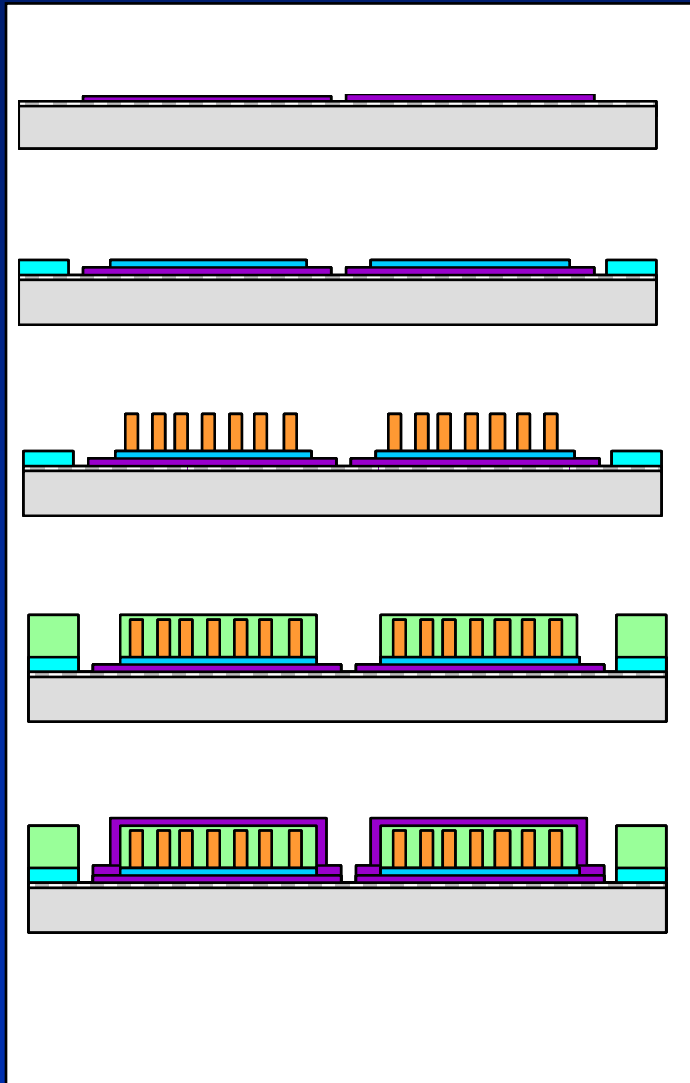
- **Stacked IC and Inductor requires:**
  - Inductor operation at high frequency ( $> 20$  MHz)
  - Size & form factor compatibility between IC and inductor ( $< 4 \text{ mm}^2$  )
  - Low Inductor profile ( $< 0.3 \text{ mm}$ )
  - Packaging scheme
- **Micro-fabricated inductor can satisfy these requirements**

# Magnetics on Silicon: Tyndall Approach

- Single layer of racetrack shaped copper coils sandwiched between layers of magnetic material
- Copper coils deposited by electroplating
- Core consists of thin film of NiFe alloy deposited by electroplating



# Overview of Fabrication Process



Layer 1: Electroplated bottom core layer

Layer 2: Insulator layer between bottom core and winding

Layer 3: Electroplated copper winding layer

Layer 4: Insulator layer between top core and winding

Layer 5: Electroplating top core layer

# Winding Technology

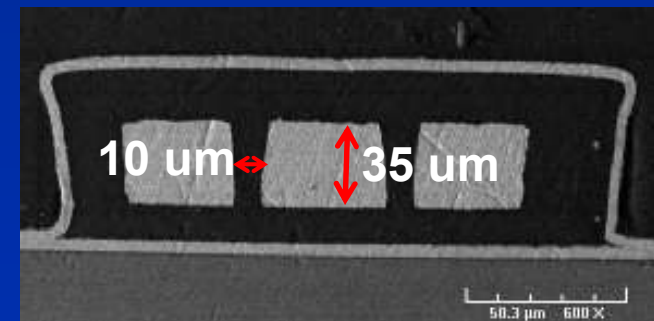
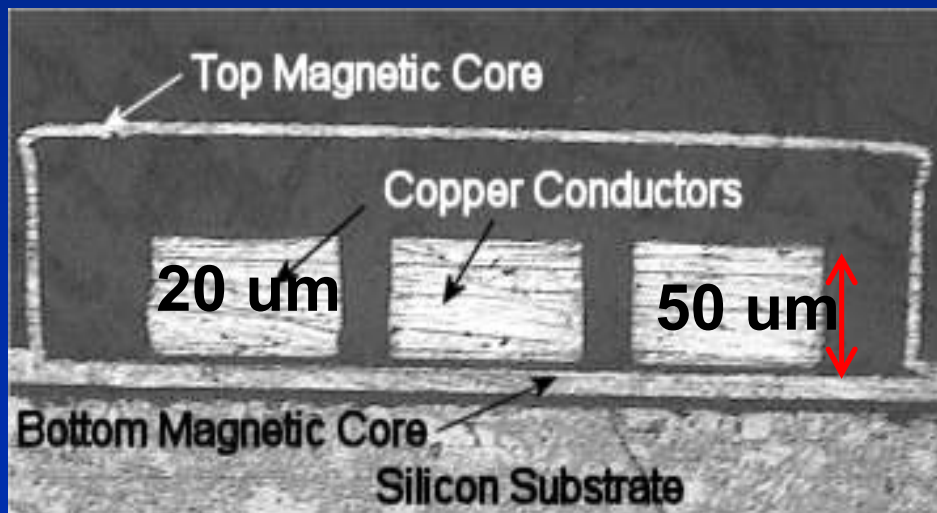
Electroplated copper

Maximum conductor thickness,  $t_m$

$50 \mu\text{m}$

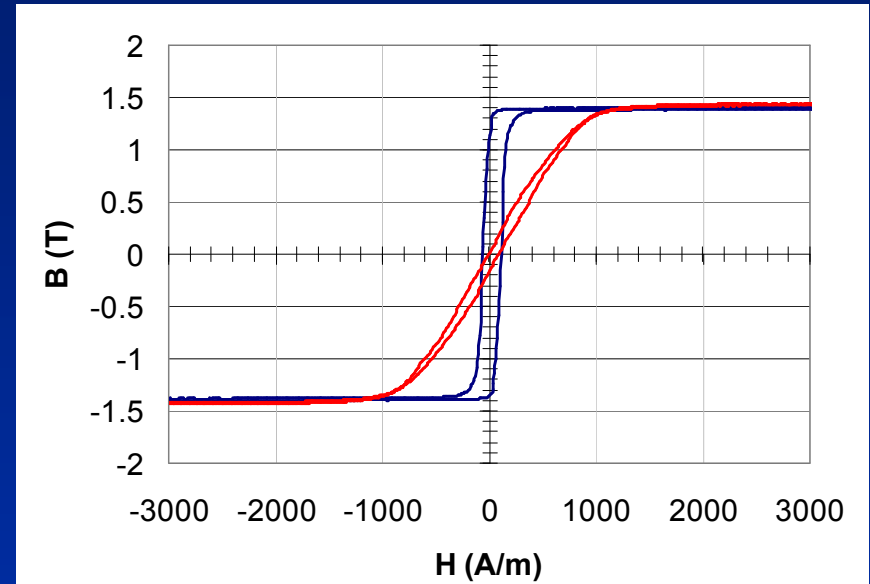
Minimum spacing – linked to thickness

$t_m/3$

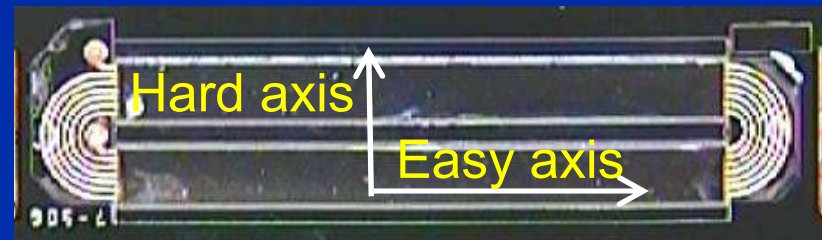


# Magnetic Core Material

Electroplated Ni <sub>45</sub> Fe <sub>55</sub>	
Saturation, B <sub>sat</sub>	1.44 T
Coercivity, H <sub>c</sub>	80 A/m
Resistivity, ρ	45 μΩ cm
Anisotropy, H <sub>k</sub>	800 A/m

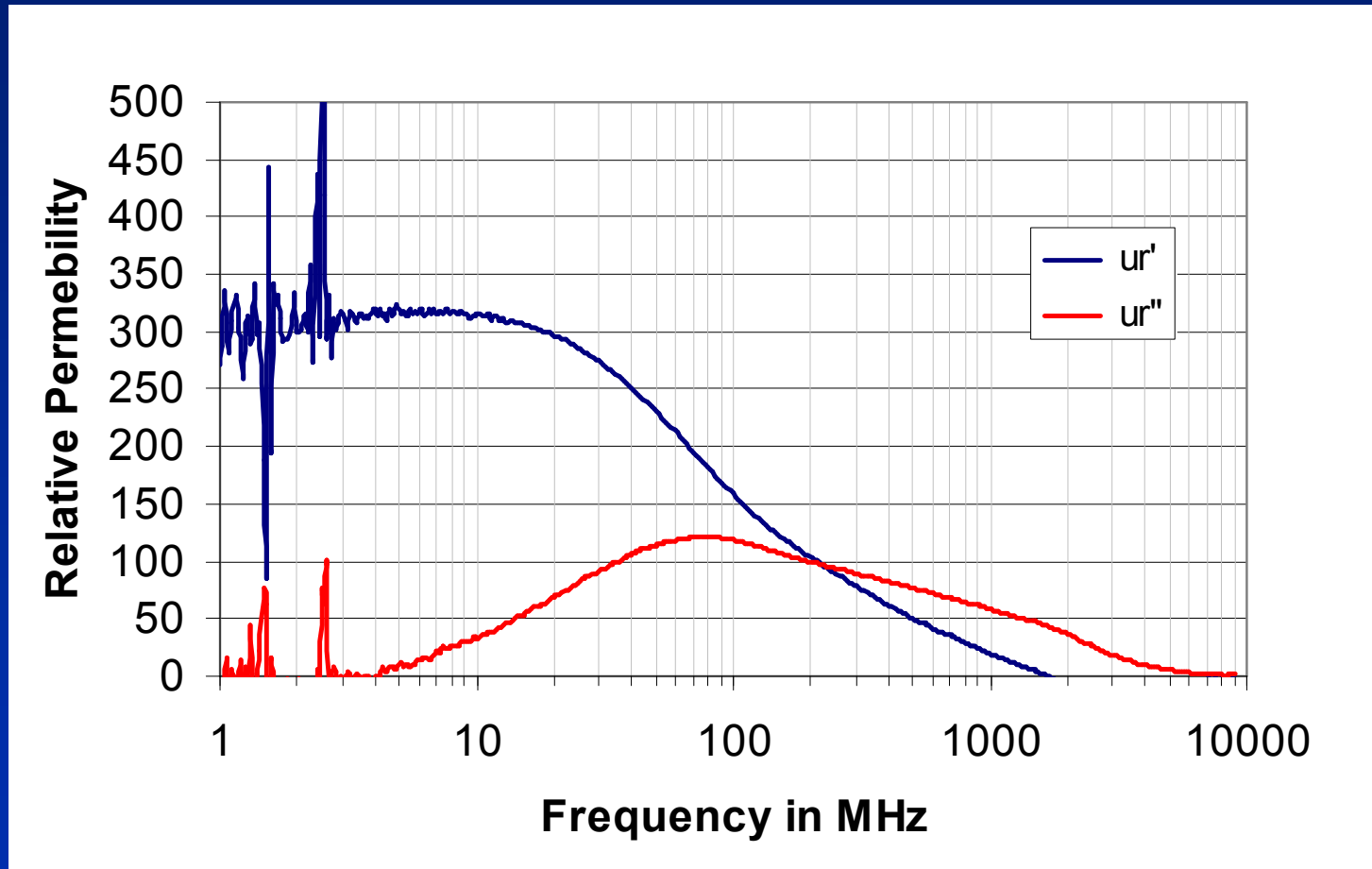


Anisotropy induced in material during deposition





# Permeability vs. frequency



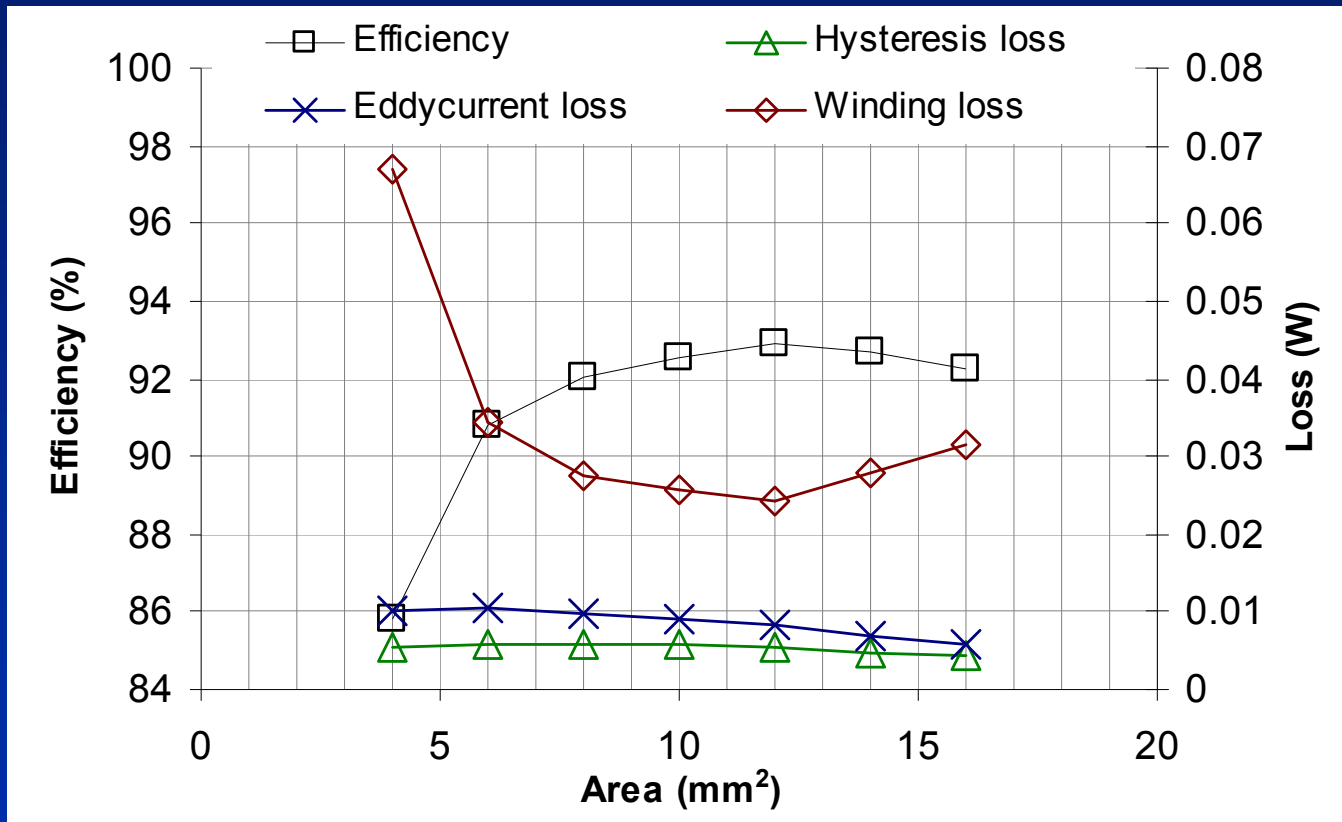
# Design Approach

- Size and Efficiency are the key design parameters
- Define Inductor Efficiency as figure of merit

$$\text{Efficiency} = \frac{\text{Converter Output Power}}{\text{Converter Output Power} + \text{Inductor Loss}}$$

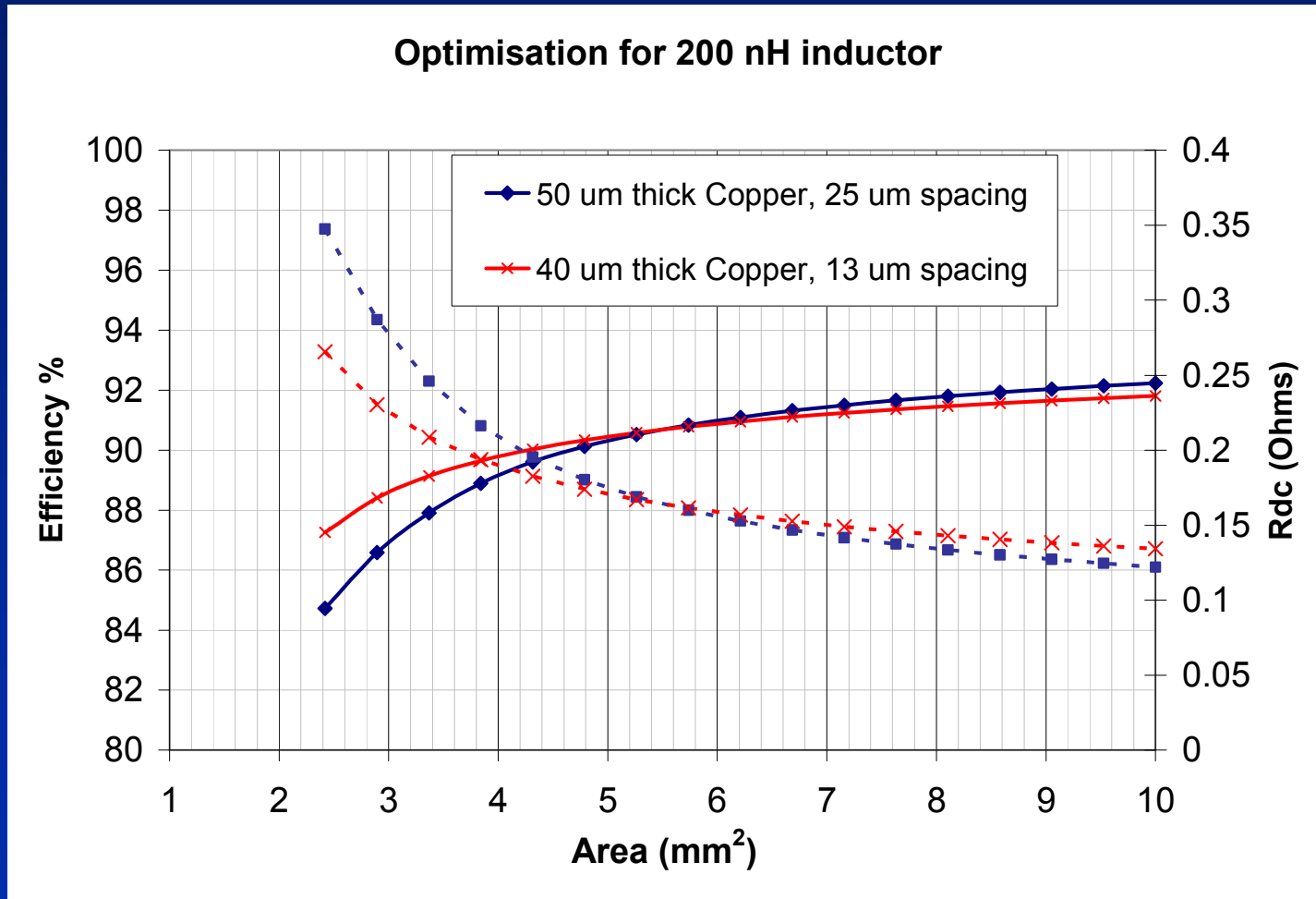
- Optimization based on analytical model for inductor
- Model Includes:
  - Core loss: Eddy currents + Hysteresis
  - Winding loss: DC + AC (6 harmonics)
- Goal of Optimization:
  - Maximize efficiency in any given area

# Efficiency-Area trade-off



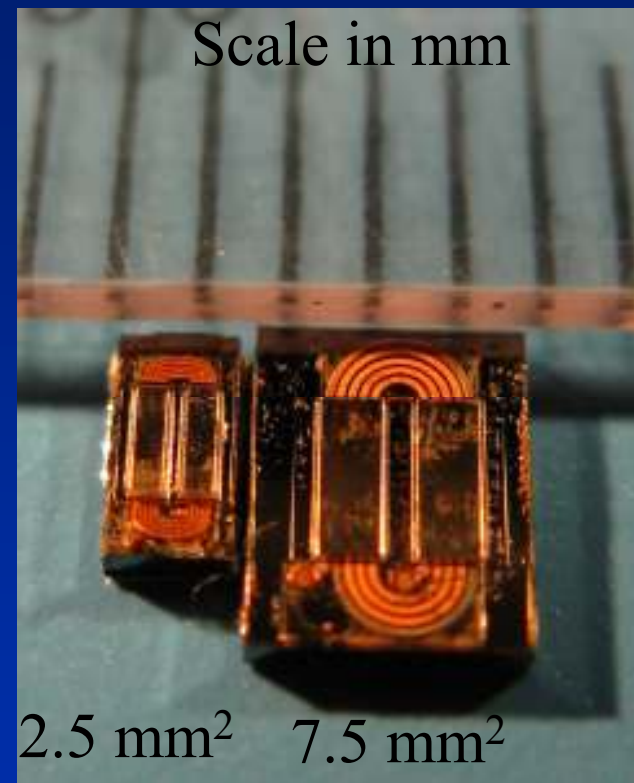
- Maximum Efficiency vs. Area,  $L = 120 \text{ nH}$
- $V_{in} = 3.6 \text{ V}$ ,  $V_{out} = 1.2 \text{ V}$ ,  $I_{out} = 500 \text{ mA}$ ,  $I_{ripple} = 0.6 I_{out}$ ,  $f = 20 \text{ MHz}$

# Micro-inductor Optimisation



# Fabricated Devices

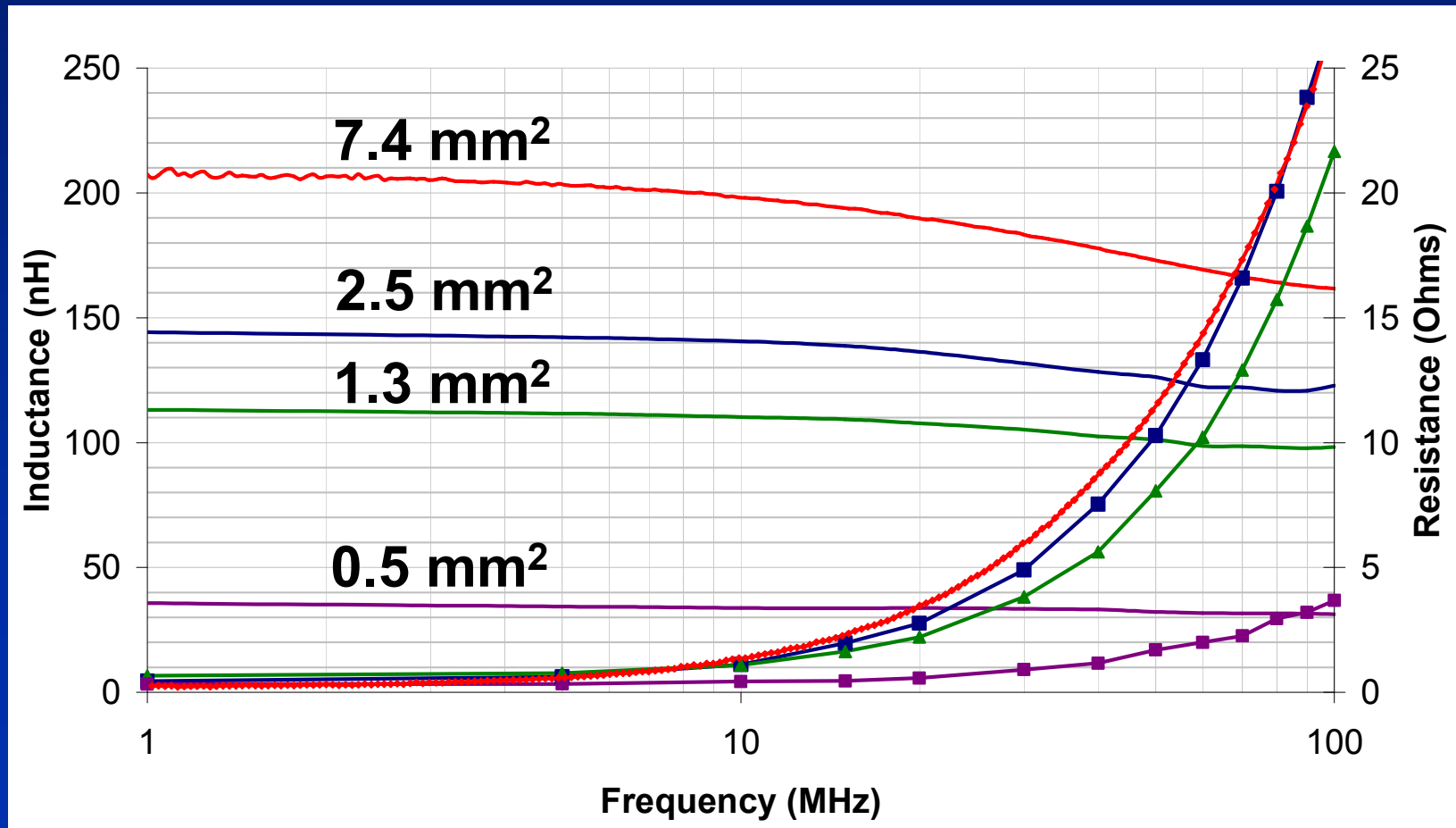
- Design Inductance range
  - $0.5 \text{ mm}^2 \rightarrow 10 - 40 \text{ nH}$
  - $1.3 \text{ mm}^2 \rightarrow 30 - 200 \text{ nH}$
  - $2.5 \text{ mm}^2 \rightarrow 30 - 200 \text{ nH}$
  - $5.5 - 10 \text{ mm}^2 \rightarrow 100 - 300 \text{ nH}$
- Designed to maximize efficiency for:
  - $V_{in} = 3.6 \text{ V}$ ,  $V_{out} = 1.2$
  - $f = 20 \text{ MHz}$



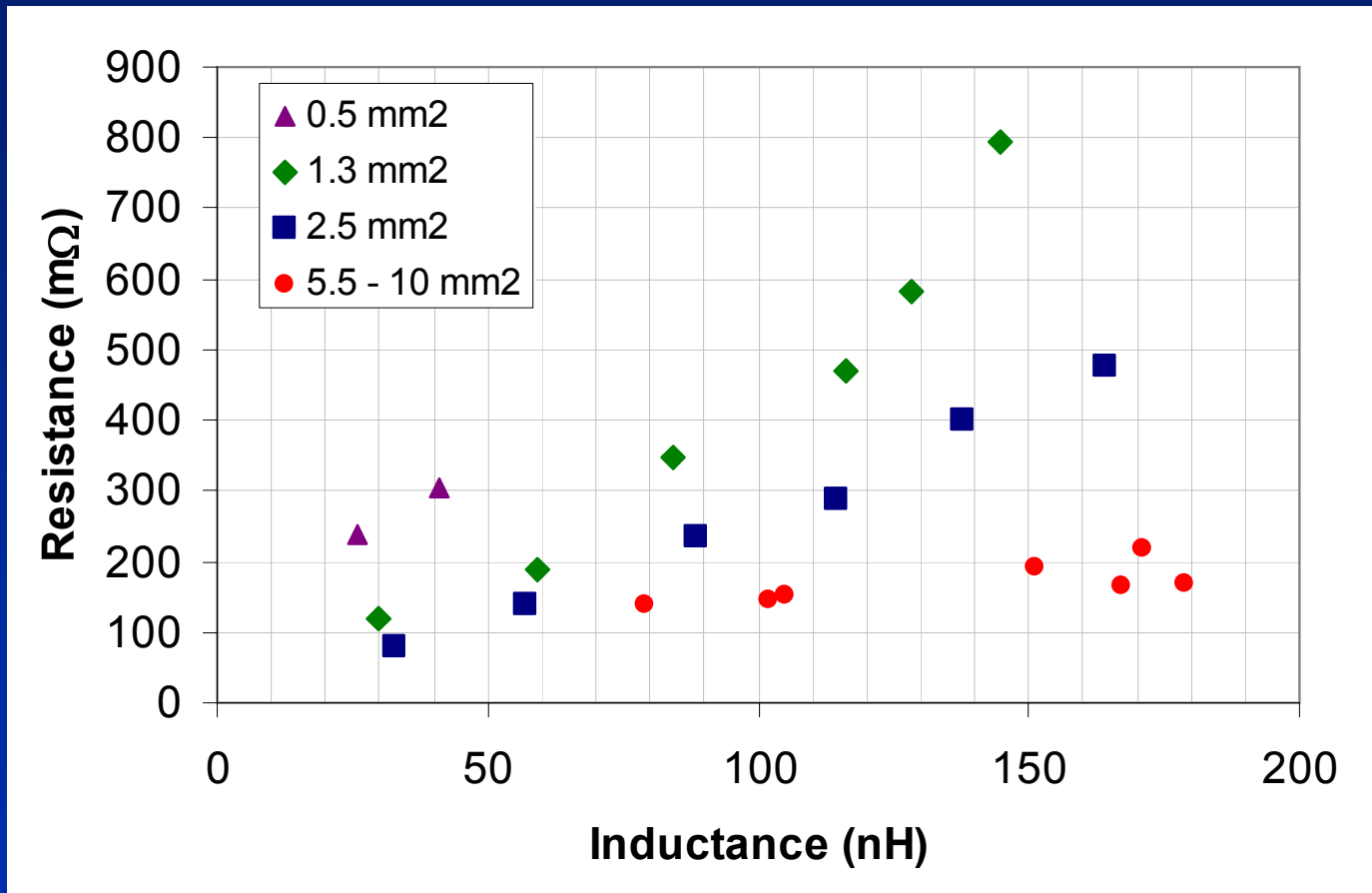
Two 140nH inductors

# Typical L and R vs. f

- Inductance and resistance vs. frequency



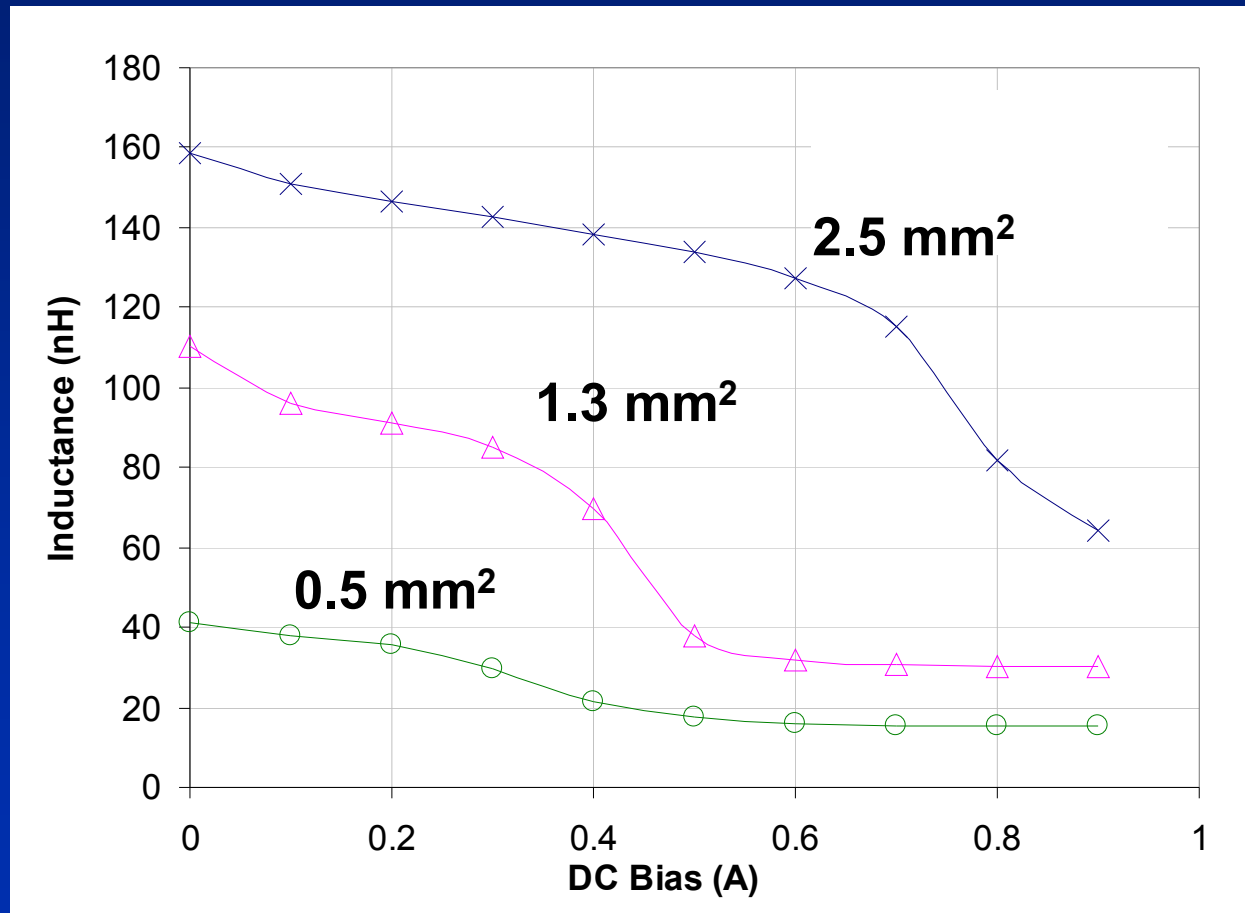
# Inductance & DC resistance



- Measured inductance vs R<sub>dc</sub> vs. area achieved to-date

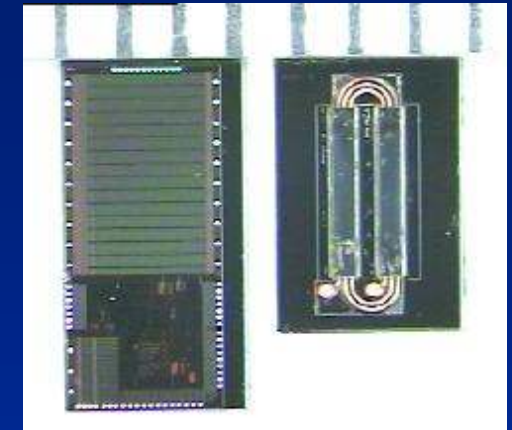
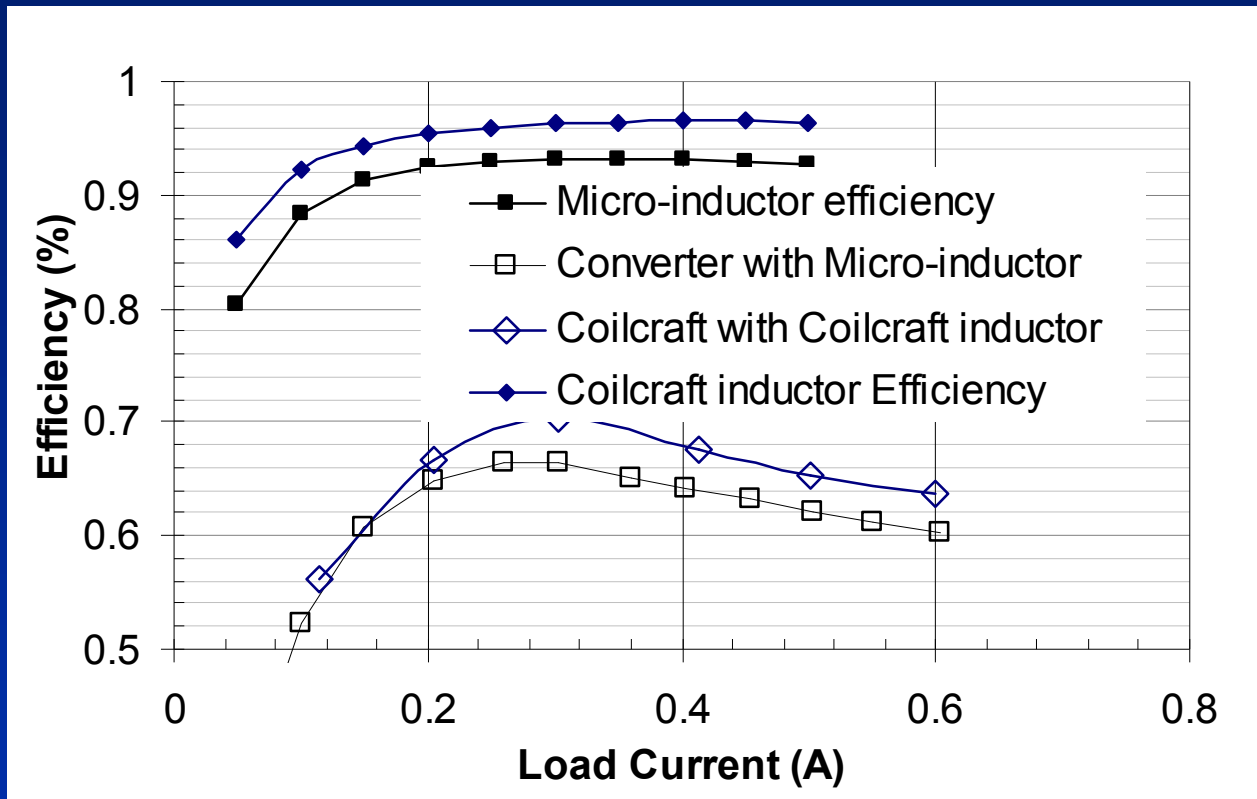
# Typical DC Bias Characterization

- Inductance at 20 MHz vs DC bias current





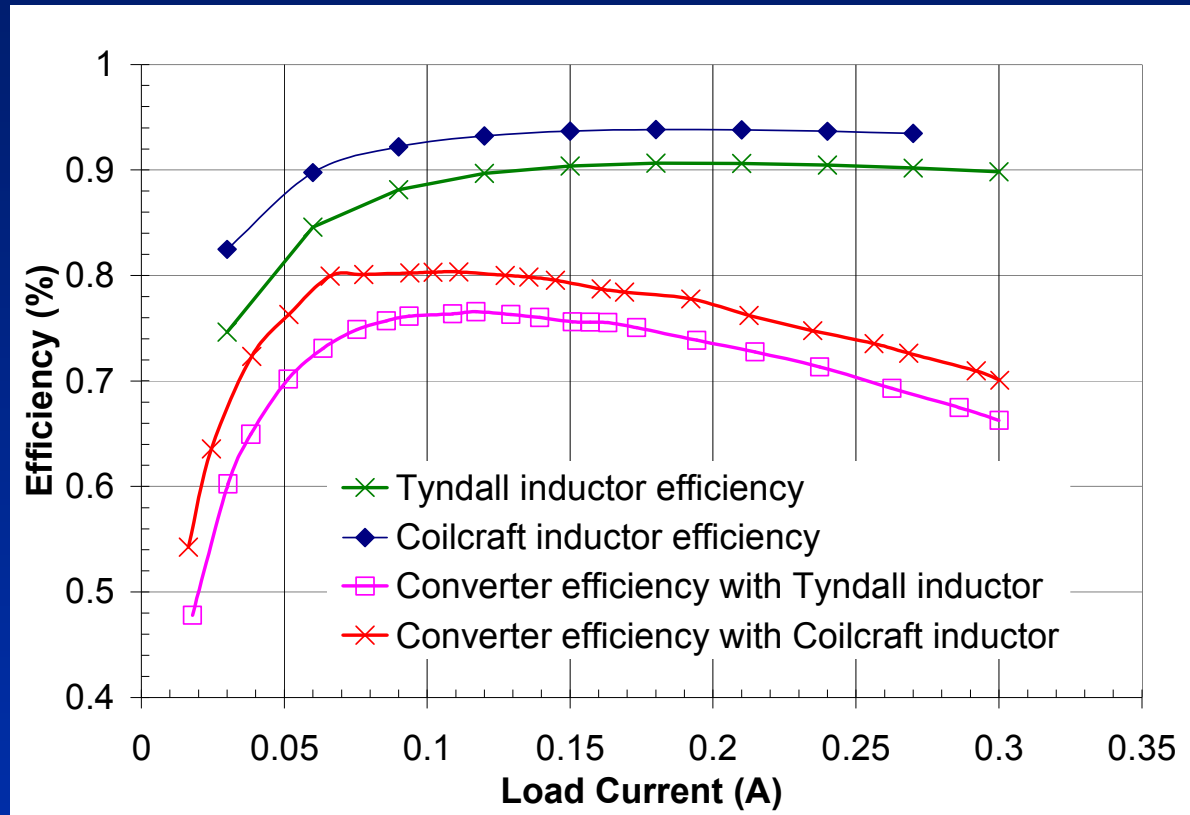
# Efficiency in Converter



110 nH micro-inductor & converter IC

- 110 nH micro-inductor (5.5 mm<sup>2</sup>) compared to 110 nH wire-wound inductor in a 20 MHz dc-dc converter
- First generation 20 MHz converter designed by PERL group in University College Cork,  $V_{in} = 2.6\text{ V}$ ,  $V_{out} = 1.2\text{ V}$

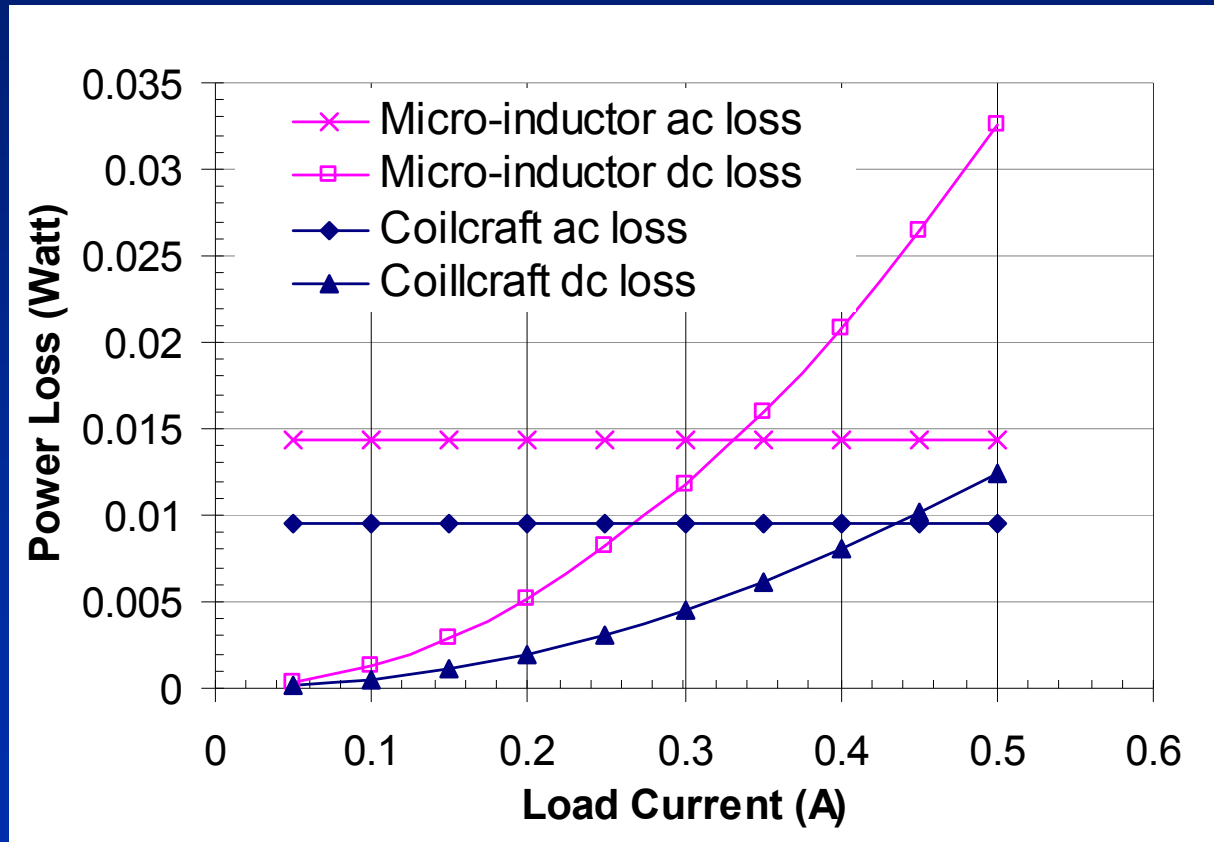
# Efficiency in Converter



- 160 nH micro-inductor (2.5 mm<sup>2</sup>) compared to 140 nH wire-wound inductor (Coilcraft 0402\_AF141) in a 20 MHz dc-dc converter
- Second generation 20 MHz converter designed by PERL group in University College Cork,  $V_{in} = 3.0$  V,  $V_{out} = 1.5$  V

# Comparison of losses

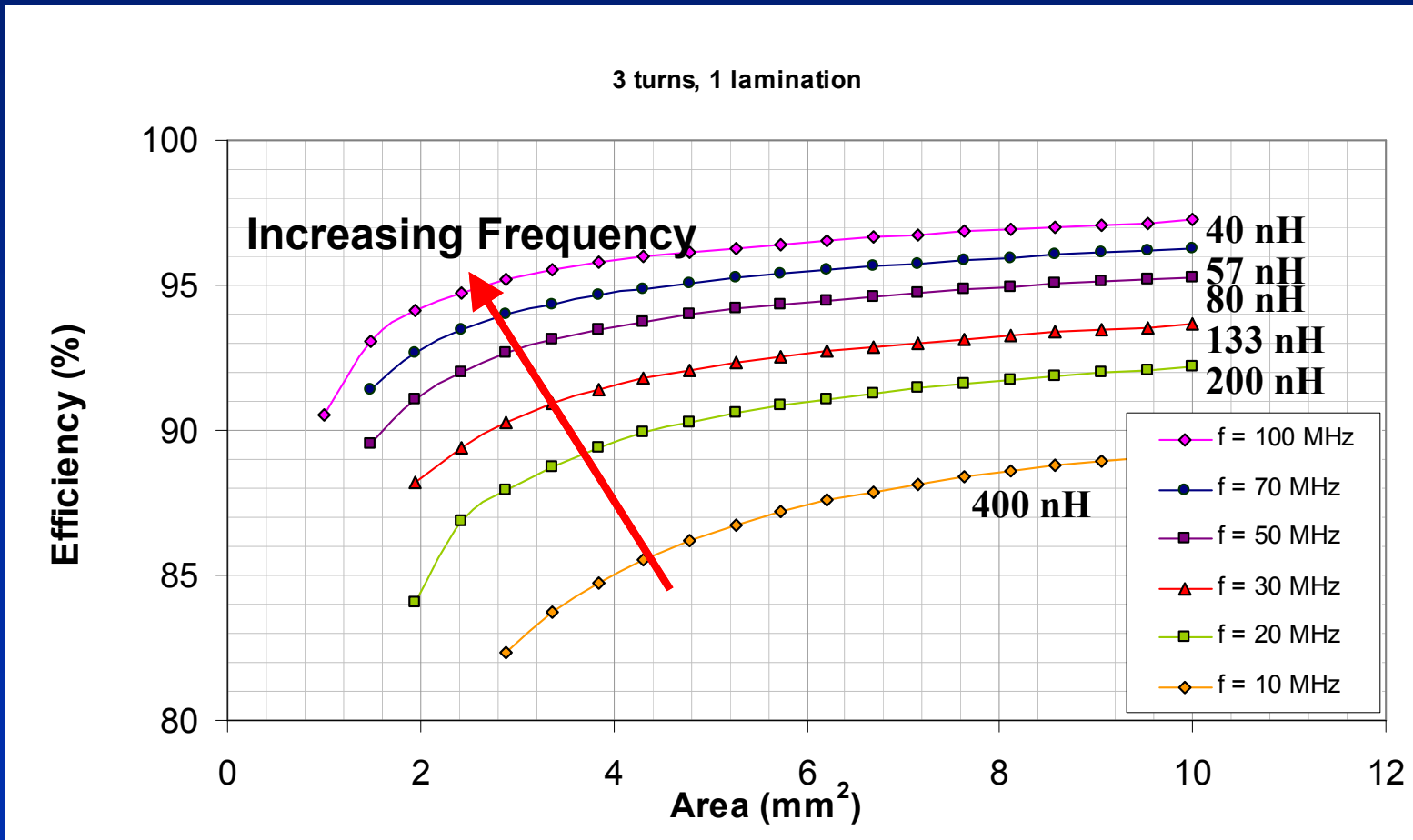
- Comparison of losses in micro-inductor to wire-wound inductor



- Further reduction in DC resistance of micro-inductor required

# Beyond 20 MHz ?

Efficiency vs. area vs. frequency for present technology



# Summary

- Extremely low profile inductor technology
- Allows stacking of inductor and converter IC
- Inductor efficiency of approximately 93% achieved at 20 MHz
- Higher efficiency and smaller size possible at higher frequencies

# Acknowledgements

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Thank you for your attention!

Questions?